

Growth and Characterization of MnBi_2Te_4 Magnetic Topological Insulator

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Abstract. We report successful growth of magnetic topological insulator (MTI) MnBi_2Te_4 single crystal by solid state reaction route via self flux method. The phase formation of MnBi_2Te_4 single crystal is strongly dependent on the heat treatment. MnBi_2Te_4 is grown in various phases i.e., MnBi_4Te_7 , $\text{MnBi}_6\text{Te}_{10}$ and MnTe as seen in powder X-ray diffraction (PXRD) of crushed resultant crystal. The Rietveld analysis shows some impurity lines along with the main phase MnBi_2Te_4 . Low temperature (10K) magneto-resistance (MR) in applied magnetic field of up to 6 Tesla exhibited –ve MR below 0.5 Tesla and +ve for higher fields. The studied MnBi_2Te_4 , MTI crystal could be a possible candidate for Quantum Anomalous Hall (QAH) effect. Here we are reporting a newly discovered magnetic topological insulator MnBi_2Te_4 having non-trivial symmetry as well as strong Spin-Orbit Coupling for QAH effect.

INTRODUCTION

Topological Insulators (TIs) are the materials which have conducting state on surface and its bulk behave like insulator [1, 2]. The existence of magnetism in topological insulator has become promising field to facilitate the exotic phenomena viz. quantized magneto electric coupling and the axion insulator state. MnBi_2Te_4 is the recently proposed candidate as magnetic topological insulator (MTI) for Quantum Anomalous Hall Effect (QAHE) to occur due to its strong Spin-orbit coupling. MnBi_2Te_4 forms an interlayer Anti-ferromagnetism (AFM) state, in which ferromagnetic (FM) Mn layers of neighbouring blocks are coupled anti-parallel to each other, converting the material into 3D topological insulator layers [3]. In case of MTIs, a magnetic layer or element is inserted among the running TI unit cells of bulk 3D topological insulators such as 3d metal doped Bi_2Se_3 , Bi_2Te_3 and Sb_2Te_3 [4-6]. The insertion of magnetic layer along running 3D bulk topological insulators shifts the Dirac position and thus alters the quantum transport properties of the parent system [7-10]. One of the most fascinating properties of the MTIs is the appearance of Quantum Anomalous Hall (QAH) effect [7-9]. QAH happens due to the finite Hall voltage created due to magnetic polarization and spin-orbit coupling, while the external magnetic field is absent. QAH is found to be in integer multiple of e^2/h which is called Landau Level [9]. MnBi_2Te_4 can be formulated as $\text{Bi}_2\text{Te}_3 + \text{MnTe}$ in which the MnTe , the magnetically ordered layer being inserted in the periodic structure at van der Waals gaps in Bi_2Se_3 3D bulk topological insulator and later [14]. MnBi_2Te_4 is the first 3D antiferromagnetic topological insulator [11-13, 15]. Interestingly, there are only some reports on MnBi_2Te_4 , in particular the single crystals [15].

EXPERIMENTAL

High-quality MnBi_2Te_4 single crystal has been grown by self-flux method through the conventional solid-state reaction route. High purity powders of Mn, Te and Bi were taken as starting material, weighed in stoichiometric ratio ground properly in glove box which is filled with argon (Ar) gas (or inert atmosphere) to avoid oxidation. Ground powder of MnBi_2Te_4 was then palletized in rectangular form using hydraulic press then sealed into a quartz tube under the vacuum pressure 10^{-5} mBar. The vacuum sealed sample then kept into electric furnace with the rate of $2^\circ\text{C}/\text{min}$. up to 1000°C , kept there for 12 h and then slowly cooled down to 600°C at a rate of $1^\circ\text{C}/\text{h}$, again sample has been hold there for 12 h. Further, the furnace was allowed to cool naturally ($20^\circ\text{C}/\text{Hour}$) to room temperature. Finally silver colored shiny crystals were obtained (shown in Figure. 1(b)) which is mechanically

cleaved for further characterizations. The heat treatment diagram of as grown single crystal of MnBi_2Te_4 is shown in Fig.1(a). XRD pattern were performed on a Rigaku Made Mini Flex-II X-ray diffractometer while the magneto resistance measurements were carried out on a Physical Property Measurement System (PPMS-10Tesla) using a close cycle refrigerator.

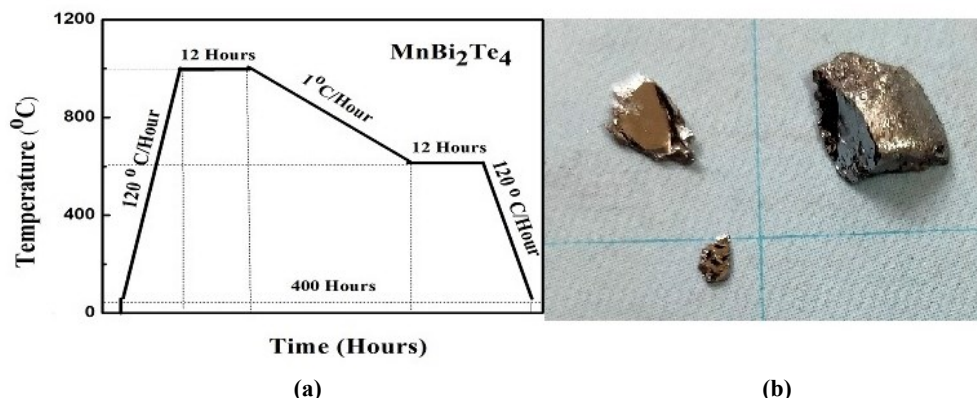


FIGURE 1.(a) Schematic heat treatment of MnBi_2Te_4 single crystal growth (b) As grown single crystal of same.

RESULTS AND DISCUSSION

Figure 2(a) depicts the X-ray diffraction pattern on flake of as grown MnBi_2Te_4 single crystal, which determines the crystallographic structure of the compound. The sharp XRD peaks of $(0, 0, 4n)$ indicate the sample has been grown along the $[001]$ plane which confirms the highly crystalline nature of the studied sample.

The single phase fullprof Rietveld analysis is carried out on the observed pattern of crushed piece of MnBi_2Te_4 crystal shown in Figure 2(b). The PXRD pattern is similar to that as observed in some recent reports for MnBi_2Te_4 self flux grown crystal. The main phase MnBi_2Te_4 is found to be crystallized in rhombohedral structure having Space group $R\bar{3}m$. The lattice parameters are $a=b=4.3882(1)\text{\AA}$ and $c=42.7125(1)\text{\AA}$. Some extra peaks of other phases i.e., $\text{MnBi}_6\text{Te}_{10}$, MnBi_4Te_7 , MnTe and Bi_2Te_3 are also observed with the main phase which we have reported elsewhere [16].

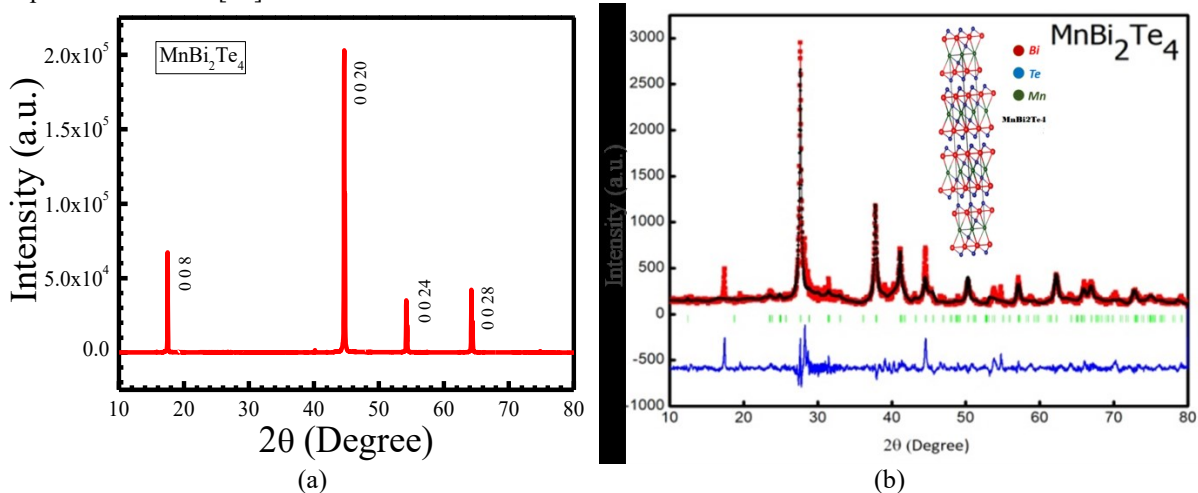


FIGURE 2. (a) X-ray diffraction pattern of flake of MnBi_2Te_4 single crystal (b) Rietveld refined PXRD pattern of MnBi_2Te_4 crystal and inset shows the unit cell of MnBi_2Te_4 .

Inset of Figure 2(b) represents the unit cells for majority phase MnBi_2Te_4 drawn by VESTA software. The simplified general formula for these homologous series of compounds is given in the form of $\text{MnTe}+n\text{Bi}_2\text{Te}_3$, with $n = 0, 1, 2, 3$ as MnBi_2Te_4 , MnBi_4Te_7 and $\text{MnBi}_6\text{Te}_{10}$. So, principally it depends upon the fact that after how many unit cells of Bi_2Te_3 , a MnTe magnetic layer is inserted.

Figure 3 shows the magneto-resistance percentage (MR%) versus applied magnetic field (H) at different temperature (10K, 20K, 50K and 200K) in applied magnetic field of up to 6Tesla for MnBi_2Te_4 single crystal. The MR (%) is calculated using the formula $\text{MR} = [\rho(H) - \rho(0)]/\rho(0)*100$, where $\rho(H)$ is the resistivity in the presence of magnetic field and $\rho(0)$ is resistivity in zero magnetic field. We observed non-saturating nearly linear positive MR value reaching up to 1.4% at 10K, whereas it reduces to around 0.8% when the temperature is

increased to 200K which is enormously less compared to as obtained in case of Bi_2Te_3 single crystal [17], shows the strong effect of magnetic ordering of Mn in MnTe layer of MnBi_2Te_4 crystal.

Inset of Figure 3 depicts the zoomed part of magneto-resistance measurement of MnBi_2Te_4 crystal in magnetic field range of ± 1 Tesla at 10K temperature. From the figure, it can be concluded that MR% decreases with increase magnetic field up to 0.2 Tesla, shows the $-ve$ MR% on further increase in magnetic field the MR% increases and shows $+ve$ MR% just above 0.5 Tesla, which further followed by almost linear behavior up to 1 Tesla magnetic field. It is also clear from the figure 3, that the MR% versus magnetic field plot for MnBi_2Te_4 crystal at low temperature shows almost linear behavior up to low field range of 0.2Tesla and shows the increment in MR% above the 0.2Tesla, which may be lead toward the quantum transport property like QAH. For confirmation about the observation of Quantum Anomalous Hall effect, detailed experiments are underway in different protocols in magnetic range up to 0.5 Tesla in very small step interval of field for MnBi_2Te_4 crystal.

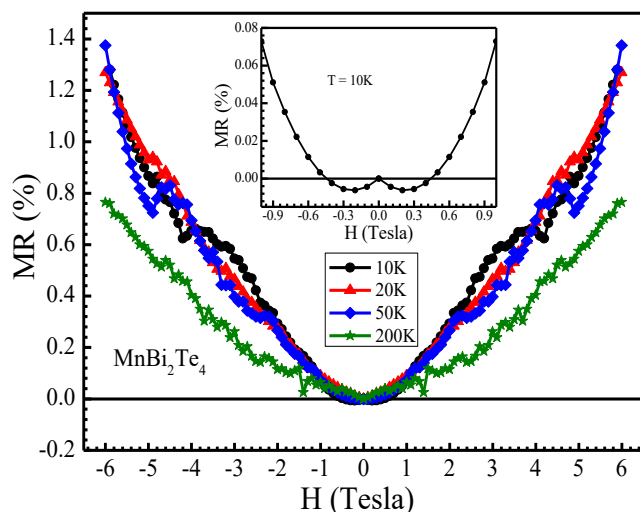


FIGURE 3. MR(%) as a function of magnetic field for the MnBi_2Te_4 single crystal at different temperatures.

CONCLUSION

In summary, in this the short communication we discuss the structural and magneto-resistance properties of the magnetic topological insulator MnBi_2Te_4 . Detailed growth parameters have been discussed through XRD analysis. As long heat treatments are required to grow high quality single crystals so our crystal quality are defensible. Low temperature (10K) MR under magnetic field of up to 6 Tesla exhibited $-ve$ MR below 0.5 Tesla and $+ve$ for higher fields. The studied MnBi_2Te_4 , MTI crystal could be a possible candidate for Quantum Anomalous Hall (QAH) effect.

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